

ABSTRACT

A lithographic projection apparatus is disclosed. The apparatus includes an illumination system for providing a beam of radiation used to irradiate a patterning device, and a first support that supports the patterning device. The patterning device capable of patterning the beam of radiation. The apparatus also includes a second support that supports a substrate, a projection system for projecting the patterned beam of radiation onto a target portion of the substrate, and a projection system positioning module that controls at least one of a position and an orientation of the projection system based on at least one of a velocity and an acceleration of the projection system.